

1. Record Nr.	UNINA990009401670403321
Autore	Haslam, Jonathan
Titolo	Russia's cold war : from the october revolution to the fall of the wall / Jonathan Haslam
Pubbl/distr/stampa	New Haven ; London : Yale University Press, 2011
ISBN	978-0-300-15997-4
Descrizione fisica	xiii, 523 p. ; 24 cm
Disciplina	3327.4700904
Locazione	FSPBC
Collocazione	XIV B 2245
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
2. Record Nr.	UNINA9911019616703321
Autore	Ostrikov K (Kostya)
Titolo	Plasma-aided nanofabrication : from plasma sources to nanoassembly / / Kostya (Ken) Ostrikov and Shuyan Xu
Pubbl/distr/stampa	Weinheim, : Wiley-VCH, c2007
ISBN	9786611088026 9781281088024 1281088021 9783527611553 352761155X 9783527611560 3527611568
Descrizione fisica	1 online resource (317 p.)
Altri autori (Persone)	XuShuyan
Disciplina	620.5 621.044
Soggetti	Low temperature plasmas Manufacturing processes Nanostructured materials Plasma engineering

Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references and index.
Nota di contenuto	<p>Plasma-Aided Nanofabrication; Contents; Preface; 1 Introduction; 1.1 What is a Plasma?; 1.2 Relevant Issues of Nanoscience and Nanotechnology; 1.3 Plasma-Assisted Synthesis of Nanomaterials; 1.4 How to Choose the Right Plasma for Applications in Nanotechnology?; 1.5 Structure of the Monograph and Advice to the Reader; 2 Generation of Highly Uniform, High-Density Inductively Coupled Plasma; 2.1 Low-Frequency ICP with a Flat External Spiral Coil: Plasma Source and Diagnostic Equipment; 2.1.1 Plasma Source; 2.1.2 Diagnostics of Inductively Coupled Plasmas</p> <p>3 Plasma Sources: Meeting the Demands of Nanotechnology3.1 Inductively Coupled Plasma Source with Internal Oscillating Currents: Concept and Experimental Verification; 3.1.1 Configuration of the IOCPS; 3.1.2 RF Power Deposition; 3.1.3 Plasma Parameters; 3.2 IOCPS: Stability and Mode Transitions; 3.2.1 Optical Emission; 3.2.2 Self-Transitions of the IOCPS Discharge Modes; 3.3 ICP-Assisted DC Magnetron Sputtering Device; 3.3.1 Enhancement of DC Magnetron Sputtering by an Inductively Coupled Plasma Source; 3.3.2 Mode Transitions in ICP-Assisted Magnetron Sputtering Device</p> <p>3.4 Integrated Plasma-Aided Nanofabrication Facility3.5 Concluding Remarks; 4 Carbon-Based Nanostructures; 4.1 Growth of Carbon Nanostructures on Unheated Substrates; 4.1.1 Process Details; 4.1.2 Synthesis, Characterization, and Growth Kinetics; 4.2 Temperature-Controlled Regime; 4.3 Single-Crystalline Carbon Nanotips: Experiment; 4.4 Single-Crystalline Carbon Nanotips: ab initio Simulations; 4.4.1 Theoretical Background and Numerical Code; 4.4.2 Geometrical Stability of Carbon Nanotip Structures; 4.4.3 Electronic Properties of Carbon Nanotips</p> <p>4.5 Plasma-Assisted Doping and Functionalization of Carbon Nanostructures4.5.1 Doping of Carbon-Based Nanostructures: Density Functional Theory Considerations; 4.5.2 Postprocessing of Carbon-Based Nanostructures: Experiments; 4.6 Synthesis of Carbon Nanowall-Like Structures; 5 Quantum Confinement Structures; 5.1 Plasma-Assisted Fabrication of AlN Quantum Dots; 5.2 Nanofabrication of Al(x) In(1-x)N Quantum Dots: Plasma-Aided Bandgap Control; 5.3 Plasma-Aided Nanofabrication of SiC Quantum Dot Arrays; 5.3.1 SiC Properties and Applications; 5.3.2 SiC Growth Modes: With and Without AlN Interlayer</p> <p>5.3.3 Quest for Crystallinity and Nanopattern Uniformity</p>
Sommario/riassunto	<p>In this single work to cover the use of plasma as nanofabrication tool in sufficient depth internationally renowned authors with much experience in this important method of nanofabrication look at reactive plasma as a nanofabrication tool, plasma production and development of plasma sources, as well as such applications as carbon-based nanostructures, low-dimensional quantum confinement structures and hydroxyapatite bioceramics. Written principally for solid state physicists and chemists, materials scientists, and plasma physicists, the book concludes with the outlook for such applications.</p>